



Laser Memory Titanium Sputtering Target Brightened Surface 99.96% Ti content

Our Product Introduction

Basic Information

- Place of Origin: China
- Brand Name: N/M
- Certification: ISO9001:2015 certification
- Model Number: CDX-20220310A
- Minimum Order Quantity: 10 piece
- Price: Negotiable
- Packaging Details: plywood case
- Delivery Time: 5-35 working days
- Supply Ability: 10000KG/month



Product Specification

- Products: Purity Titanium Target
- Key Words: High Purity Titanium Target Titanium Sputtering Target
- Application: Liquid Crystal Display
- Technique: Grinding Machine
- Application 1: Glass Coating
- Application 2: Laser Memory
- Application 3: Electronic Control Devices,
- Surface: Machine Brightened Surface
- Highlight: **Laser Memory Zirconium Target, Brightened Surface Tantalum Target, 99.96% Ti Target**



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Product Description

High Purity Titanium Target Titanium Sputtering Target

We can provide round titanium target, square titanium target, rectangular titanium target, or according to your requirements or drawings.

Tolerance	+/-0.01mm
Surface	Polished, Cleaning, CNC lathe surface, Pickled, bright
Dimensions	according customer's request.
Ti content(%)	99.96% 99.98% 99.99%
Density	4.51g/cm ³
Color	titanium original color
Titanium Sputtering Target Target Customizable High Purity	



Provide quality inspection report like this with the goods, which shows the chemical composition and physical properties

宝鸡圣德鑫钛金属材料有限公司
Baoji Quality Metals Co., Ltd

质量证明书 Quality Certificate

证书编号 (Certificate No.): CDX20210515-1ZJ

合同号 Contract No.	产品名称 Description	牌号 Designation No.	批号 Lot No/锭号 Heat No.	状态 Condition	规格 Size(mm)	数量 Quantity	产品标准 Product Standard
CDX20210425GA	钛靶板	GR1	CDX20-108	M	/	sample	ASTM B348
室温力学性能 Tensile test	试验温度 (℃) Test Temperature	抗拉强度 Rm (MPa) Tensile Strength	屈服强度 Rp0.2 (MPa) Yield Strength	断后伸长率 A(%) Elongation	断面收缩率 Z (%) Reduction of area	水压试验 Hydraulic pressure test	扩口试验 Expanding test
	Result	/	/	/	/	合格	合格
其它 Others	弯曲试验 Bend Test	低倍组织 Macrostructure	高倍组织 Microstructure	外形尺寸 Dimensional Inspection	表面质量 Visual Inspection	探伤检验 Ultrasonic Inspection	压扁试验 Flattening test
	/	/	/	合格	合格	ok	/
化学成分 Chemical Composition (%)							
Result	Ti	Al	Sn	/	/	/	Fe
	Remainder	/	/	/	/	/	0.13
C							
0.013							
N							
0.0007							
H							
0.001							
O							
0.075							
Residual element							
≤0.10							
≤0.40							
编制: 李海魁 Prepared by				批准: 宝鸡圣德鑫钛金属材料有限公司 Approved by		报告日期: 2021.5.15 Report Date	

100% quality inspection, quality assurance.

Professional titanium manufacturing experience.

Because we only make titanium, we are more professional in titanium

ISO9001:2015 certification

Friendly customer service and short delivery time.

Titanium sputtering targets are mainly used in the electronics and information industries, such as integrated circuits, information storage, liquid crystal displays, laser memory, electronic control devices, etc.; they can also be used in the field of glass coating; they can also be used in wear-resistant materials, high temperature resistance Corrosion, high-end decorative products and other industries.

High-purity and high-density sputtering targets include:

Sputtering target (purity: 99.9%-99.999%)

Magnetron sputtering coating is a new type of physical vapor coating method. Compared with evaporation coating method, it has obvious advantages in many aspects. As a relatively mature technology that has been developed, magnetron sputtering has been applied in many fields. Titanium sputtering target

Sputtering Technology Titanium Sputtering Targets

Sputtering is one of the main technologies for the preparation of thin film materials. It uses ions generated by an ion source to accelerate and aggregate in a vacuum to form a high-speed energy ion beam, bombard the solid surface, and exchange kinetic energy between ions and solid surface atoms. The atoms on the solid surface leave the solid and are deposited on the surface of the substrate. The bombarded solid is the raw material for preparing the thin film deposited by the sputtering method, which is called the sputtering target. Various types of sputtered thin film materials have been widely used in semiconductor integrated circuits, solar photovoltaics, recording media, flat-panel displays, and workpiece surface coatings.



Provide the most accurate data reports

Baoji Luox Quality Metals Co., Ltd.



+8613911115555



test@test.com



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GAOYA INTERSECTION, BAOTAI ROAD GAOXIN DISTRICT, BAOJI SHAANXI CHINA